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## ABSTRACT OF THE DISCLOSURE

A carbazole derivative of the following formula (1),

wherein  $R^1$  and  $R^2$  individually represent a hydrogen atom or a monovalent organic group, or  $R^1$  and  $R^2$  form, together with the carbon atom to which  $R^1$  and  $R^2$  bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and  $R^3$  represents a hydrogen atom or a monovalent organic group. The carbazole derivative is suitable as an additive for increasing sensitivity of a chemically amplified resist. A chemically amplified radiation-sensitive resin composition, useful as a chemically amplified resist, comprising the carbazole derivative is also disclosed.